IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney Docket No.: UCF-306RCE
Application Serial No.: 10/082,658
Filed: 10/19/2001
First Named Inventor: Martin Richardson
Examiner: Thomas, Courtney D.
Group: 2882
For: EUV,XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA PRODUCED FROM LIQUID METAL SOLUTIONS, AND NANO-SIZE PARTICLES IN SOLUTIONS

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner of Patents
and Trademarks
Washington DC 20231

Sir:

Pursuant to 37 CFR §§ 1.97 and 1.98, record is being made below in a form PTO-1449 of documents which the Patent Office may wish to consider in connection with examination of the above-identified patent application. It is respectfully requested that the cited documents be carefully considered by the Examiner and made of record in this case. As provided in § 1.97(g), no representation is made or intended that a thorough art search was made. As provided in 37 C.F.R. § 1.97(h), this Supplemental Information Disclosure Statement does not constitute an admission of any kind, and specifically is not an admission that the documents listed on the attached PCT-1449 are, or are considered to be, material to the patentability of the above-identified patent application, as defined in 37 C.F.R. § 1.56(b).

Copies of the cited references were previously submitted to the USPTO in the parent application No.: 10/082,658 filed: 10/19/2001 and placed in the file. Applicants claim priority to said application under 35 U. S. C. §120. Accordingly, copies of those documents are not provided with this Statement pursuant to 37 CFR § 1.98(d).

It is respectfully requested that the cited documents be carefully considered by the Examiner and made of record in the case.

Respectfully submitted,

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ORM PTO-1449

ATTORNEY DOCKET NO. UCF-306CIP

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON
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FORM PTO-1449

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SUPPLEMENTAL FORM PTO-1449

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